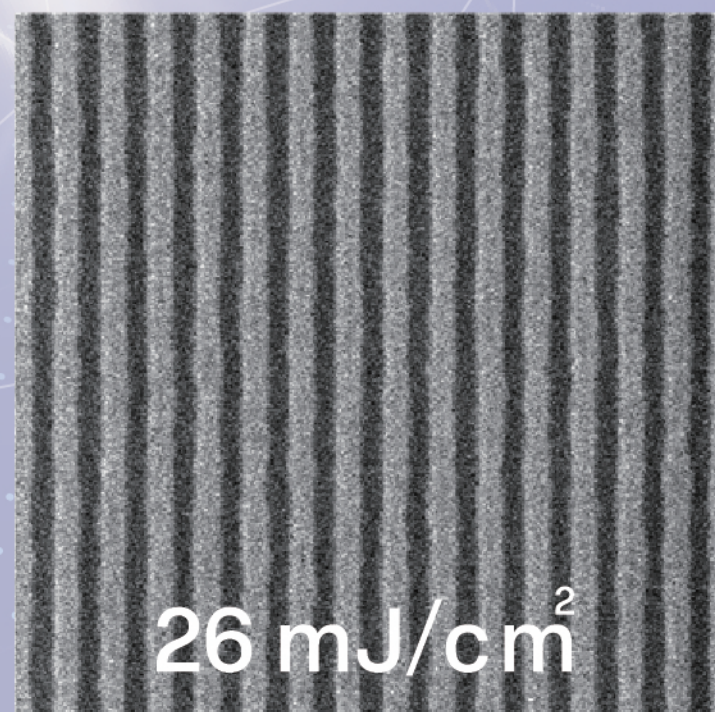


JSR EUV Photoresist

Challenge for Sensitivity and Defectivity

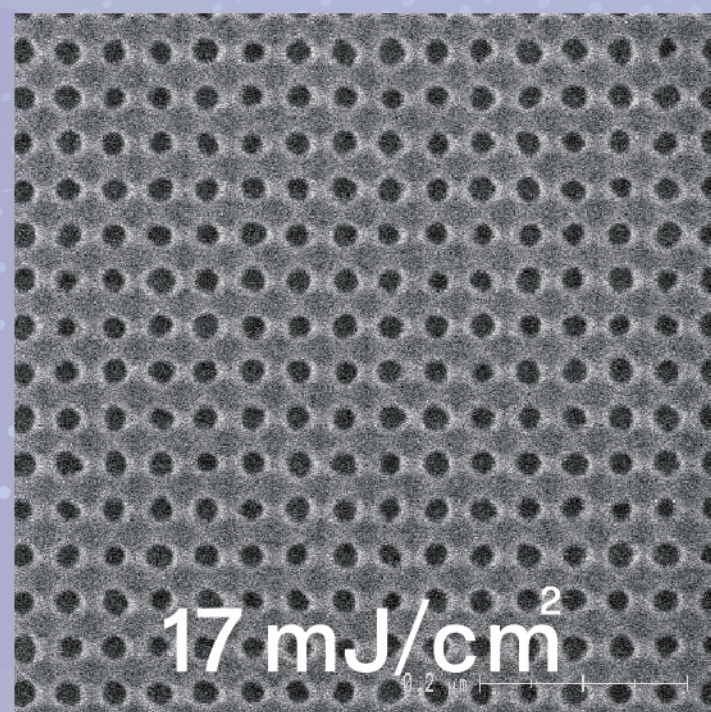
15 nm L/S



26 mJ/cm²

Substrate: Organic HM
Resist FT: 35 nm

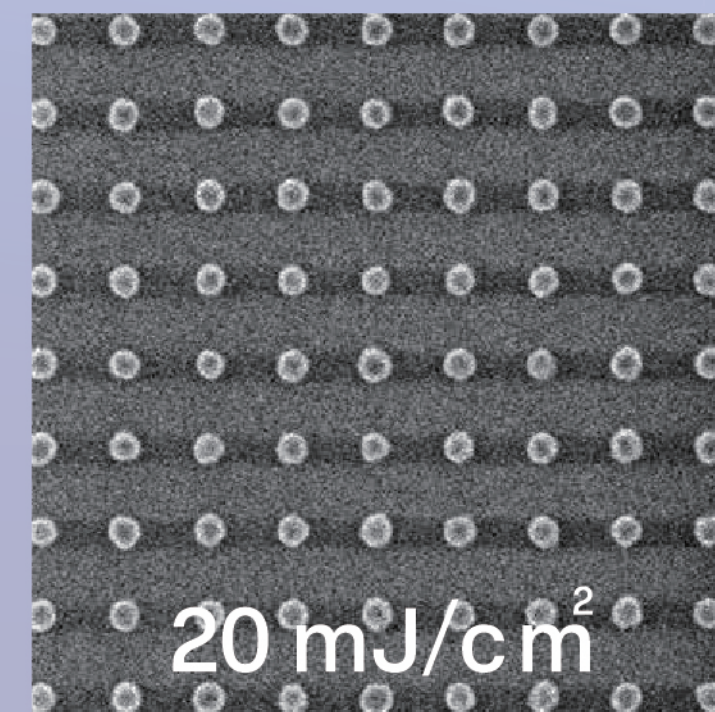
21 nm C/H



17 mJ/cm²

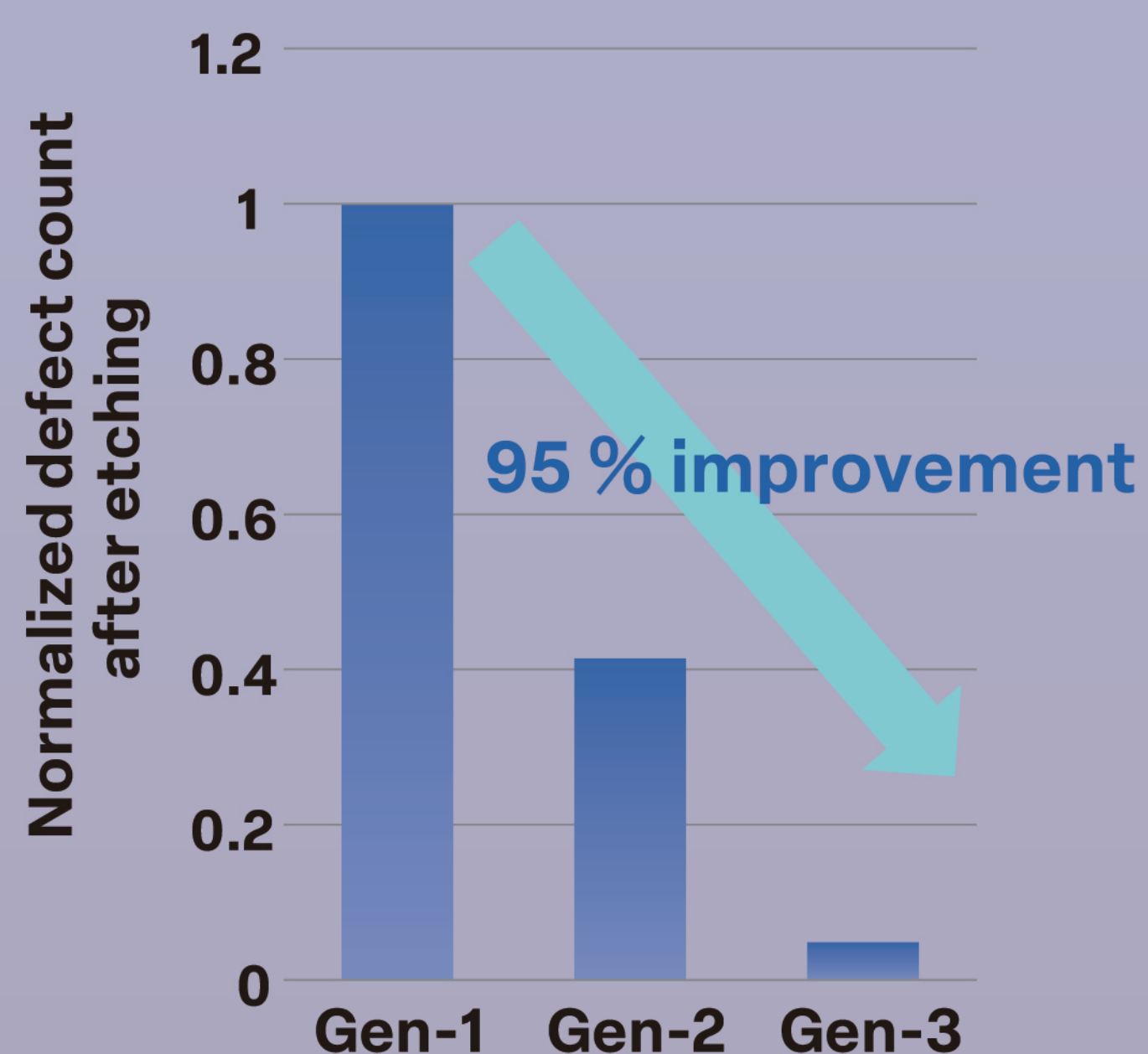
Substrate: ML/Organic HM
Resist FT: 50 nm

21 nm Pillar

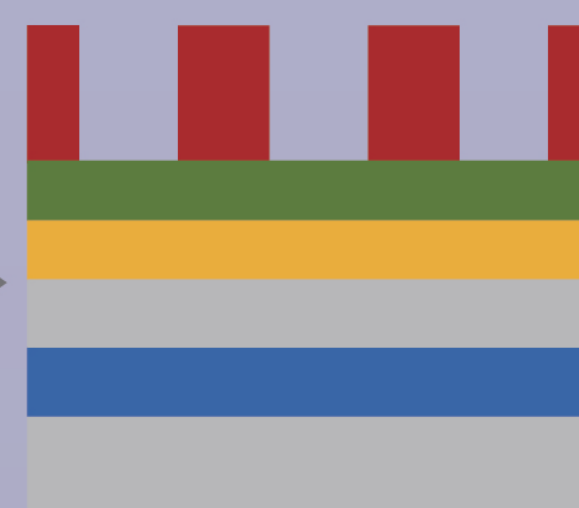


20 mJ/cm²

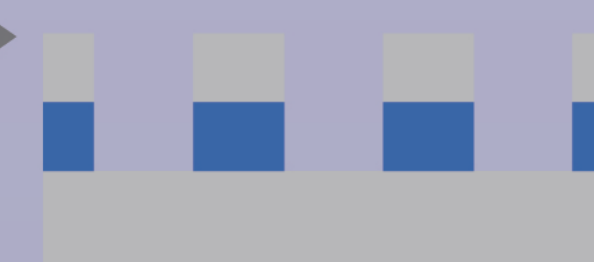
Substrate: ML/Organic HM
Resist FT: 50 nm



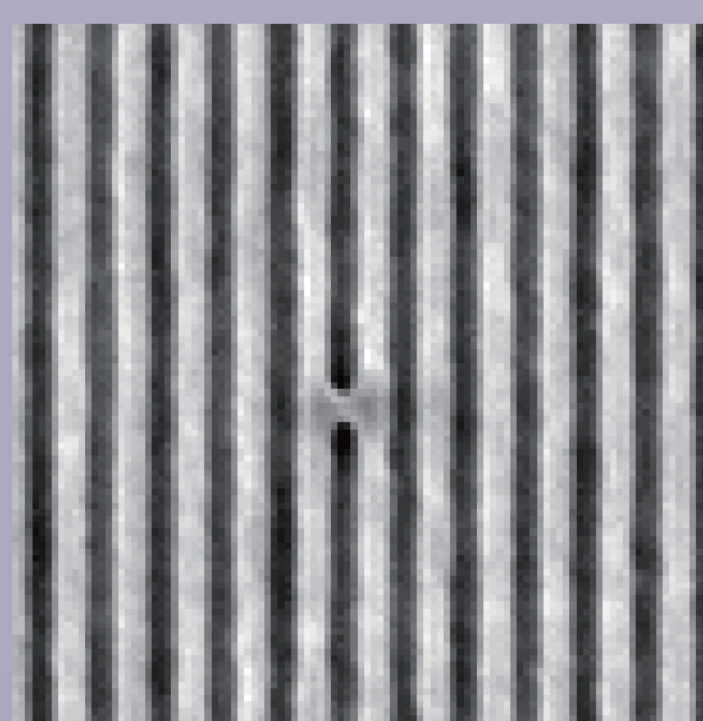
Litho



Etch



imec



Target CD: 18 nm LS
Exposure: NXE3300 (NA0.33)

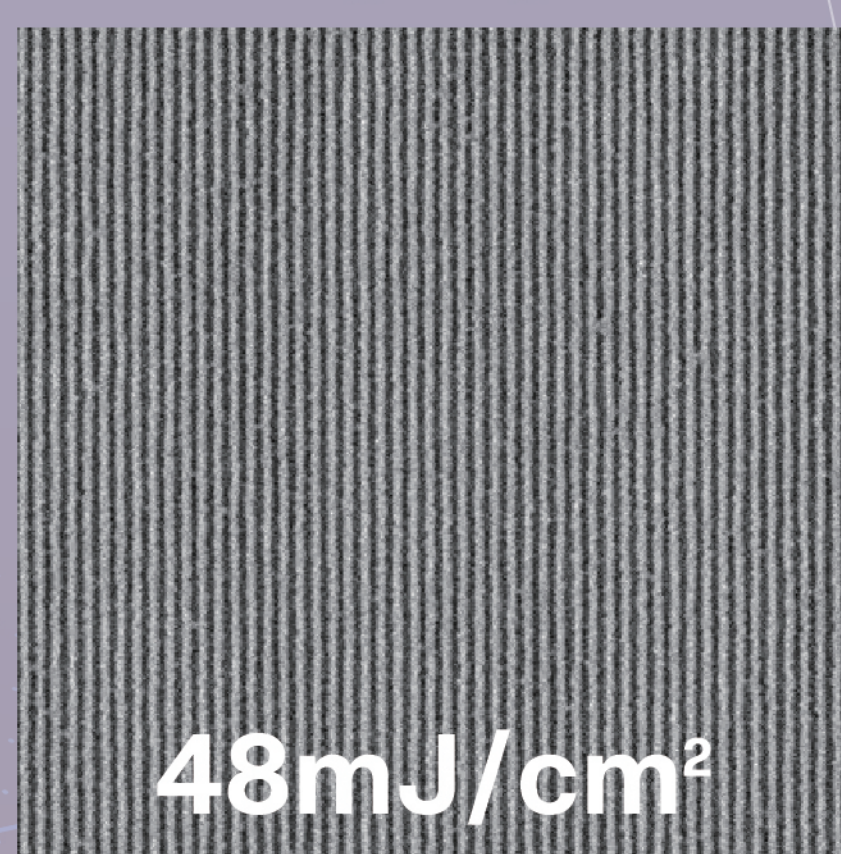
Challenge for Next Generation Photoresist

Inpria Corporation

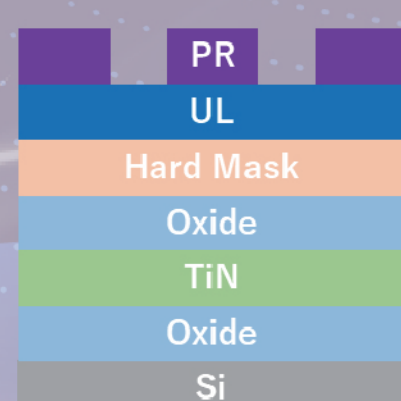
Development and manufacturing of “metal-based EUV resists”

NEW

8nm L/S
EXE5000@High NA Lab



48mJ/cm²



imec

inpria



Oregon, US